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INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				APPLICANT Uzodinma Okoranyanwu et al.			
				FILING DATE 03/28/2001		GROUP ART UNIT 2878	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
		09/819,342		Shields et al			03/28/01
		09/819,343		Gabriel et al			03/28/01
		09/819,344		Okoroanyanwu et al			03/28/01
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		5,003,178	03/26/91	Livesay	250	492,300	
FOREIGN PATENT DOCUMENTS							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION YES NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
		Livesay, W. R., "Large-area electron-beam source," Journal of Vacuum Science & Technology B, Vol. 11, No. 6, Nov./Dec. 1993, pp. 2304-2308, American Vacuum Society					
		Yang, J. J. et al, "Electron Beam Processing for Spin-on Polymers and Its Applications to Back-End-of-Line (BEOL) Integration," Materials Research Society Symposium Proceedings, Vol. 511, 1998, pp. 49-55, Materials Research Society					
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		Grün, Von A. E., "Lumineszenz-photometrische Messungen der Energieabsorption im Strahlungsfeld von Elektronenquellen Eindimensionaler Fall in Luft," Zeitschrift für Naturforschung, Vol. 12a, 1957, pp. 89-95, Publisher: Zeitschrift für Naturforschung; full English Translation attached (11 pgs.)					
EXAMINER				DATE CONSIDERED			
* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.							

Title: IMPROVING SEM INSPECTION AND ANALYSIS OF
PATTERNED PHOTORESIST FEATURES

Inventor(s): Okoroanyanwu et al. Dkt. No. 039163-0405 (F0945)
Appl. No.: 09/820,143

KDNL

- Information Disclosure Statement (3 pgs.);
- Form PTO-1449 (1 pg.) and 13 References.

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